

contacting at least one side of said substrate with a liquid comprising water, ozone and an additive acting as a scavenger, wherein the proportion of said additive in said liquid is less than 1% molar weight of said liquid; and

maintaining said liquid at a temperature less than the boiling point of said liquid.

(Twice Amended) A method for removing organic contaminants from a substrate, the organic contaminants resulting from a previous lithographic step, the method comprising the steps of:

contacting at least one side of said substrate with a liquid comprising water, ozone and an additive acting as a scavenger, wherein said liquid is comprised substantially of water; and maintaining said liquid at a temperature less than the boiling point of said liquid.

(Twice Amended) A method for removing organic contaminants from a substrate, the organic contaminants resulting from a previous lithographic step, the method comprising the steps of:

holding said substrate in a tank; and

filling said tank with a fluid comprising water, ozone and an additive acting as a scavenger, and wherein the fluid is comprised substantially of water.

McDONNELL BOEHNEN HULBERT & BERGHOFF 300 South Wacker Drive, Suite 3200 Chicago, Illinois 60606 (312) 913-0001